Korean International Semiconductor Conference & Exhibition
on Manufacturing Technology 2025

KISM 2025 BUSAN

Re:Innovation of Semiconductor Manufacturing for AI Ecosystem

[ThA1] Nanoscale Thin Film Deposition VI	
Session Date	November 13 (Thu.), 2025
Session Time	09:00-10:10
Session Room	Room A (Capri Room, 2F)
Session Chair	Prof. Young-Rae Cho (Pusan Nat'l Univ., Korea)

[ThA1-1] [Invited] **09:00-09:30**

Multi-Threshold Voltage (V_{ht}) Engineering Using ALD TaN-Based HKMG Gate Stack for Advanced Logic and DRAM Devices

Changhwan Choi (Hanyang Univ., Korea)

[ThA1-2] [Invited] **09:30-09:50**

Ultrathin Freestanding Ceramic Membranes for Yield Enhancement in Extreme Ultraviolet Lithography

Seul-Gi Kim, Hyun-Mi Kim (KETI, Korea), Yongkyung Kim (KETI and Hanyang Univ., Korea), Hye-Young Kim, Kihun Seong (KETI and Sungkyunkwan Univ., Korea), Su Min Lee (KETI, Korea), Jonghyuk Yoon (KETI and Sungkyunkwan Univ., Korea), and Hyeongkeun Kim (KETI, Korea)

[ThA1-3] [Invited] **09:50-10:10**

Transforming Semiconductor Manufacturing with AI: Changing the Paradigm of Next-Generation Semiconductor Processes

Jinwoo Kim, Changheon Han, Kwan Lee, Nuri Oh, Changmin Jung, Taehang Ahn, Minje Kim, and Beomju Yu (HEX A.I. Labs Inc., Korea)